

FORM PTO-1449 (SUBSTITUTE)

U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE

INFORMATION DISCLOSURE STATEMENT BY APPLICANT (37 CFR 1.98(b))

Attorney Docket No	.:
EHF 2001,0167	P

Applic. No.

09/873,230

Applicant

Norbert Benesch et al.

Filing Date
June 4, 2001

Group Art Unit

2621

## **U.S. PATENT DOCUMENTS**

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Norbert Benesch et al.

Filing Date June 4, 2001 Group Art Unit 2621

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FORM PTO-1449 (SUBSTITUTE) Attorney Docket No.: Applic. No. EHF 2001.0167 P 09/873,230 U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE Applicant Norbert Benesch et al. INFORMATION DISCLOSURE STATEMENT BY APPLICANT Filing Date Group Art Unit (37 CFR 1.98(b)) June 4, 2001 **U.S. PATENT DOCUMENTS EXAMINER** SUB FILING PATENT NO. DATE **PATENTEE** CLASS INITIALS **CLASS** DATE Α 4,964,726 10/23/90 Kleinknecht et 15 McNeil et al. 12 В 5,703,692 12/30/97 JS C 5,830,611 11/03/98 Bishop et al. D Ε F G Н FOREIGN PATENT DOCUMENT SUB TRANSL. DOCUMENT NO. COUNTRY CLASS DATE CLASS YES | NO 15 J 198 24 624 A1 02/25/99 Germany K Х 11 0 874 396 A2 10/28/98 Europe М

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